



TFW

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q90414

Hiroyuki AKAGAWA

Appln. No.: 10/549,901

Group Art Unit: 2812

Confirmation No.: 7222

Examiner: Not yet assigned

Filed: September 20, 2005

For: SUBSTRATE FOR RETICLE AND METHOD FOR MANUFACTURING SUBSTRATE,
AND MASK BLANK AND METHOD FOR MANUFACTURING MASK BLANK

REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT

ATTN: Office of Initial Patent Examination

Filing Receipt Correction

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

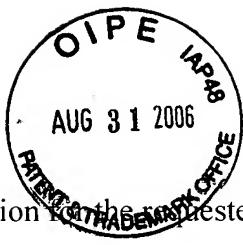
Sir:

We enclose a copy of the Official Filing Receipt for the above-identified application and
request the following correction:

Please add assignee as follows:

Assignee:

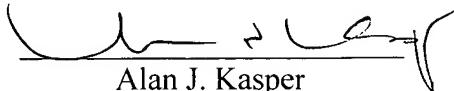
HOYA CORPORATION



Verification of the requested correction is indicated on the Declaration and

Assignment filed September 20, 2006.

Respectfully submitted,



Alan J. Kasper
Registration No. 25,426

SUGHRUE MION, PLLC
Telephone: (202) 293-7060
Facsimile: (202) 293-7860

WASHINGTON OFFICE

23373

CUSTOMER NUMBER

Date: August 31, 2006



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UNITED STATES DEPARTMENT OF COMMERCE
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APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/549,901	09/20/2005	2812	1500	Q90414	3	16	2

CONFIRMATION NO. 7222

23373
 SUGHRUE MION, PLLC
 2100 PENNSYLVANIA AVENUE, N.W.
 SUITE 800
 WASHINGTON, DC 20037

FILING RECEIPT



OC000000019409888

Date Mailed: 06/28/2006

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please mail to the Commissioner for Patents P.O. Box 1450 Alexandria Va 22313-1450. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Hiroyuki Akagawa, Tokyo, JAPAN;

ASSIGNEE: HOYA CORPORATION

Power of Attorney: The patent practitioners associated with Customer Number 23373.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/03617 03/18/2004

Foreign Applications

JAPAN 2003-077005 03/20/2003

If Required, Foreign Filing License Granted: 06/24/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is **US10/549,901**

Projected Publication Date: 10/05/2006

Non-Publication Request: No

Early Publication Request: No

Title

Substrate for reticle and method of manufacturing the substrate, and mask blank and method of manufacturing the mask blank

Preliminary Class
428



PROTECTING YOUR INVENTION OUTSIDE THE UNITED STATES

Since the rights granted by a U.S. patent extend only throughout the territory of the United States and have no effect in a foreign country, an inventor who wishes patent protection in another country must apply for a patent in a specific country or in regional patent offices. Applicants may wish to consider the filing of an international application under the Patent Cooperation Treaty (PCT). An international (PCT) application generally has the same effect as a regular national patent application in each PCT-member country. The PCT process **simplifies** the filing of patent applications on the same invention in member countries, but **does not result** in a grant of "an international patent" and does not eliminate the need of applicants to file additional documents and fees in countries where patent protection is desired.

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Applicants may wish to consult the USPTO booklet, "General Information Concerning Patents" (specifically, the section entitled "Treaties and Foreign Patents") for more information on timeframes and deadlines for filing foreign patent applications. The guide is available either by contacting the USPTO Contact Center at 800-786-9199, or it can be viewed on the USPTO website at <http://www.uspto.gov/web/offices/pac/doc/general/index.html>.

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Assignment

Whereas, I/We, HIROYUKI AKAGAWA of Tokyo, Japan, hereinafter called assignor(s), have invented certain improvements in
SUBSTRATE FOR RETICLE AND METHOD FOR MANUFACTURING SUBSTRATE, AND MASK BLANK
AND METHOD FOR MANUFACTURING MASK BLANK

as set forth in an application for Letters Patent of the United States of America corresponding to international application No. PCT/JP2004/003617 filed on March 18, 2004; and

Whereas, HOYA CORPORATION,

7-5, Naka-Ochiai 2-chome, Shinjuku-ku, Tokyo 161-8525, Japan

(assignee), desires to acquire the entire right, title, and interest in the application and invention, and to any United States patents to be obtained therefor;

Now therefore, for valuable consideration, receipt whereof is hereby acknowledged,

I/We, the above named assignor(s), hereby sell, assign and transfer to the above named assignee, its successors and assigns, the entire right, title and interest in the application and the invention disclosed therein for the United States of America, including the right to claim priority under 35 U.S.C. §119, and I/we request the Director – U.S. Patent and Trademark Office to issue any Letters Patent granted upon the invention set forth in the application to the assignee, its successors and assigns; and I/we will execute without further consideration all papers deemed necessary by the assignee in connection with the United States application when called upon to do so by the assignee.

I/We hereby authorize and request our attorneys SUGHRUE MION, PLLC of 2100 Pennsylvania Avenue, NW, Washington, DC 20037-3213 to insert here in parentheses (Application number _____ and Confirmation number _____, filed _____) the filing date and application number of said application when known.

Date: September 12, 2005

s/ HIROYUKI AKAGAWA

Hiroyuki Akagawa

Date:

s/

Date:

s/

Date:

s/

Date:

s/